



Press Releases

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VISIT US AT BOOTH #6144 AT SEMICON WEST, SAN FRANCISCO

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NIKON INSTRUMENTS TO LAUNCH DEDICATED SEMICONDUCTOR INSPECTION TECHNOLOGIES GROUP (SITECH)

MELVILLE, NY, July 9, 2002 – Nikon Instruments Inc. today announced the formation of the Nikon Semiconductor Inspection Technologies Group (Nikon SITECH). The newly formed group is an aggressive move by Nikon Instruments to offer more comprehensive service and support to their current and future customer base, including a fourfold increase in sales and technical support, as well as to broaden the U.S. distribution of Nikon's advanced semiconductor inspection products.

The new group will be located in the Phoenix, Arizona area, a semiconductor hub, and will allow Nikon to offer an unprecedented focus on training, demonstrations, and service application support, as well as the infrastructure to sell direct to customers.

Takashi Tanzawa was named Executive Vice President and will lead the technologies group. Prior to this appointment, Mr. Tanzawa was Manager of Strategy for the Nikon Instruments Company in Japan. "Nikon's SITECH group demonstrates Nikon's enhanced commitment to the future of the semiconductor industry that involves aggressive product development, superior training and technical support and affords Nikon the opportunity to capitalize on new business and market opportunities," said Mr. Tanzawa.

According to President and CEO of Nikon Instruments, Hiro Kusaka, "SITECH is a critical step to expand Nikon Instruments and to create a division that is more focused, flexible and responsive to our customers and the semiconductor industry. We are confident in its ability to make a significant impact on our business."

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About Nikon Instruments, Inc.

Nikon Instruments, Inc. is a world leader in precision optics manufacturing. Nikon is committed to providing its customers with quality products that include high-performance semiconductor wafer handling and inspection equipment; microscopes for bioscience research and industrial applications; advanced high-speed, vision-based and optical measuring tools; land surveying instruments; and diagnostic equipment for optometrists. For more information, visit the Nikon website at www.nikonusa.com. Product related inquiries can be directed to Nikon Instruments at 800 52 NIKON.

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OPTISTATION-3000 SERIES OFFERS HIGH-PRECISION, ULTRA-FAST INSPECTION FOR 300MM WAFERS

MELVILLE, NY, July 15, 2002 --- Nikon's Optistation-3000 Wafer

Inspection System is a set of tools optimally designed to fit all 300mm inspection needs. OST-3100, an off line single FOUP inspection tool featuring a small footprint and low price; and OST-3200, a two FOUP system that meets 300mm factory automation needs.

All models offer the ultimate in high-precision, high throughput macro and micro inspection, plus ultra-clean transfer and rapid inspection in an operator-friendly environment. All models also offer an integrated mini environment Compatible with Nikon's award-winning DART wafer inspection software and other software packages, the Optistation-3000 tools are flexible for complete compatibility with most line layouts.

The flexible Optistation-3000 systems allow superb brightfield and darkfield observation as standard, plus optional differential interference contrast (DIC) observation. A newly designed deep ultraviolet (DUV) module is available to meet 0.10µm design rule. Front and back-side macro inspection is a standard feature on the OST-3100 and OST-3200. In

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addition, flexible layouts on the single load port systems allow the load ports to be placed on the side or rear of the OST-3100 and OST-3200, allowing the tools to easily adapt to various cleanroom layouts.

Optistation-3000 [series](#) is remarkably easy to use, thanks to its Windows® NT software platform and advanced ergonomic operation. Even novice operators can learn to program the wafer inspection station in minutes. Touch screen technology and motorized optical observation techniques allow for simple and comfortable observation. The operation-keys layout is ideally located for easy operation. Plus, the OST-3000 series offers a comfortable inspection posture for all users, with tilting eyepiece tubes, optimal microscope eyepoint and compliance with SEMI S8-0600 guidelines. The system can be fully automated for loading, magnification change, brightfield/darkfield switching, aperture stop, field stop and polarizer capabilities.

All systems are equipped with Nikon's patented CFI60 optical system, providing high numerical apertures with long working distances. This results in images of better clarity, higher contrast and minimal flare, even at extremes of magnification.

The system is exceptionally clean, surpassing Class I cleanroom-compatible specifications. The Optistation-3000 series relies on fewer moving parts, DC servo motors and stepper motors for its ultra-clean operation, and features flow-through ventilation and hands-off operation to keep it free of contaminants in daily use. Also, all Nikon inspection tools

comply with the latest SEMI safety and ergonomic standards and are CE marked.

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Press Release

Nikon Corporation Wins Intel's Preferred Quality Supplier Award

SAN JOSE, California, March 22, 2004 - Nikon Corporation was named a recipient of Intel Corporation's Preferred Quality Supplier (PQS) award for outstanding performance in providing products and services deemed essential to Intel's success. The company was awarded for its efforts in supplying Intel with lithography exposure equipment and measuring instruments. Nikon Corporation and 28 additional PQS award winners will be honored at a celebration in Burlingame, Calif., on March 23.

"Nikon's continuous efforts to improve our products and customer support systems have been recognized by Intel, and we are very proud to receive this award for the 2nd year in a row," said Michio Kariya, Nikon Corporation president of Precision Equipment Company.

"Congratulations to Nikon for receiving PQS recognition two years in a row," said Peter Silverman, Intel director, Lithography Capital Equipment Development. "This is a significant achievement because Intel increases the very demanding requirements for PQS status each year. Nikon's continued focus on enabling technologies and affordability in support of our One Generation Ahead strategy has helped to make Intel a success. We look forward to working together with Nikon to successfully meet industry challenges in the years ahead."

The PQS awards are part of Intel's Supplier Continuous Quality Improvement (SCQI) process that encourages suppliers to strive for excellence and continuous improvement. To qualify for PQS status, suppliers must score 80 percent on a report card that assesses performance and ability to meet cost, quality, availability, delivery, technology and responsiveness goals. Suppliers must also manage and deliver on a challenging improvement plan and a quality systems assessment. Additional information about the SCQI program is available at <http://supplier.intel.com/quality>.

Intel will also recognize PQS award winners on March 23 with an advertisement in the U.S., Europe and Asian editions of The Wall Street Journal.

About Intel

Intel, the world's largest chip maker, is also a leading manufacturer of computer, networking and communications products. Additional information about Intel is available at www.intel.com/pressroom.

About Nikon

Since 1917, Nikon Corporation has been a leader in optical glass manufacturing. With continued growth and expertise, Nikon now offers a

diverse range of industrial instruments, including steppers and scanners, microscopes and measuring instruments to complement a full line of semiconductor manufacturing related equipment.

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FOR IMMEDIATE RELEASE

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**NIKON INSTRUMENTS ANNOUNCES RECORD SALES OF ITS NRM-3100
OVERLAY INSPECTION MEASUREMENT SYSTEM**

Marks Major Milestone in 300mm Semiconductor Wafer Manufacturing

MELVILLE, NY, September 10, 2004 – Nikon's Semiconductor Inspection Technologies Group (SITECH) today announced that a major US semiconductor manufacturer has placed a multi-million dollar order for Nikon's NRM-3100 Overlay Inspection Measurement system. The sale marks an important milestone in SITECH's move into global 300mm semiconductor wafer manufacturing.

"The success of the NRM-3100 underscores Nikon's commitment to anticipate the rapidly changing needs of our customers and to deliver products that are flexible and extensible," said Takeshi Kamiya, general manager, SITECH "We're pleased to be able to support the development and production of advanced chips on 300mm wafers."

The NRM-3100 is SITECH's latest product featuring high precision overlay metrology capability. The device measures lithographic exposure overlay precision with respect to previous exposure layers. The NRM-3100's optical quality minimizes lens aberration and delivers sub-nanometer precision. The product's camera and image processing capability speeds the move and measure time to 1.3 seconds, and provides unmatched throughput of more than 150 wafers per hour.

The NRM-3100 has been designed for process flexibility and productivity in the high paced 300mm production environment. The optional Bridge tool is designed to provide an upgrade path from 200mm to 300mm wafer overlay inspection. The product is installed at leading chip manufactures around the world.

The NRM-3100 is a distinguished member of Nikon's Semiconductor Inspection Technologies product line which includes the following products.

- ➡ AMI-2000 Automatic Macro Inspection System, a unit featuring high detection sensitivity with an exclusive diffracted light detection system to detect pattern variation due to defocus by the stepper, or an uneven coating by the coater.
- ➡ The Optistation 3100 Wafer Inspection System with Nikon's renowned CFI60 optics producing crisp, clear images with high contrast and minimal flare.
- ➡ The Optistation 7 IC Wafer Inspection System Dual, a 300 mm fabrication compliant unit featuring a feeder arm transfer unit offering high throughput with a new macro illumination system allowing for thin film observation and defocus detection as well as detection of particulates and scratches on both front and backside.
- ➡ The Optistation V, a cost-effective inspection unit featuring a small footprint and a full range of Optical techniques. Accommodates bright Field, Dark Field, Nomarski DIC as well as Confocal observation all on one system. The high precision wafer alignment and DART defect review packages offer review capabilities for virtually all file formats

The Nikon NRM-3100 Overlay Inspection Measurement system is currently available.

About Nikon Instruments Inc.

Nikon Instruments Inc. is a global leader in the development of advanced optical technology. Its product line includes microscopy equipment, digital imaging, precision measuring and semiconductor wafer-handling equipment. Nikon is committed to providing technologically advanced instruments that offer optimal versatility, performance and productivity. Nikon combines state-of-the-art capabilities with innovative designs to produce optically superior, ergonomically friendly products for cutting-edge scientific research, medical and industrial applications. For more information visit the Nikon website at www.nikonusa.com. Product related inquiries can be directed to Nikon Instruments at 800-52-NIKON.

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Nikon Integrates Metrology, Inspection Groups at Ariz. Facility

Online staff -- 4/1/2005

Electronic News

Melville, N.Y.-based microscopy, digital imaging, measuring and wafer-handling equipment provider Nikon Instruments Inc. today said it would integrate its two high precision industrial metrology businesses -- Semiconductor Inspection and Nexiv Vision Measuring Systems -- under its Sitech division in Tempe, Ariz.

Nikon said it expects this move to improve customer responsiveness by coordinating applications engineering and service departments, product management and sales teams.

The new Sitech division is to be lead by Takeshi Kamiya, general manager who reports to Lee Shuett, executive VP of the company. Shuett reports to Fumitaka Akeda, president of the company.

"This important change will enable these two businesses to share the outstanding facilities at our Tempe office, and by combining our resources, personnel and facilities, position Nikon for broader growth within the semiconductor and vision systems measuring vertical business," Shuett said in a statement.

Two new departments have also been established within Sitech: vision systems and semiconductor inspection, meant to increase Nikon metrology applications integration across industrial market segments including semiconductor, automotive, defense, medical device and electronic components.

Michael Metzger, general manager of the company's industrial department is to be responsible for marketing for the vision/measuring systems, semiconductor inspection and industrial microscopy, to remain at the company's headquarters in N.Y

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NIKON INSTRUMENTS ANNOUNCES RECORD SALES OF ITS 300MM OPTICAL INSPECTION SYSTEMS

Marks Major Milestone in 300mm Semiconductor Wafer Manufacturing

MELVILLE, NY, January 15, 2005 – Nikon's Semiconductor Inspection Technologies Group (SITECH) today announced that they have shipped 150 300mm Optical Inspection tools to several US based semiconductor manufacturers. The sale marks an important milestone in SITECH's presence in the global 300mm semiconductor wafer manufacturing.

The success of our Optical Inspection line of tools continues to lead the way in unparalleled performance for the semiconductor industry. With over 400 200mm tools in the US market and now achieving 150 300mm tools reassures that Nikon's superior performance, low CoO and the industries highest reliability numbers are the best value to our customers.

The complete 300mm line of Optical Inspection tools include; Ost-3200, Ost-3100 and OST-7's. Our tools allow the customer to inspect their wafers for macro defects on the front side, back side and edge of the wafer. After the Macro inspection the wafers are transferred to the microscope side to inspect for Micro defects under several choices of magnification. The tools have the option to view defects using DUV illumination which allows for even smaller defect inspection.

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NIKON INSTRUMENTS ANNOUNCES THE P3: A PRECISION PATTERN PROFILER OPTIMIZING TOTAL LITHOGRAPHY PERFORMANCE

MELVILLE, NY, July 10, 2006 – Nikon Instruments, Inc., (www.nikonusa.com) a world leader in the development of advanced optical technology, today announced a new lithography inspection platform designed improve product yield by capturing yield-limiting defects.

Nikon's Precision Pattern Profiler (P3) reduces time to detection, time to correction, time to results, and ultimately, time to market. As design rules and process windows continue to shrink, IC manufacturers face many challenges in achieving and maintaining yields and profitability while moving to new processes. The challenges have become more difficult because fabs must capture a wider range of problems on patterned wafers – physical defects, electrical defects, and even macro defects, which can ruin an entire wafer rather than just a die.

"Nikon's new P3 allows our customers' to save time and money while optimizing valuable resources," said Glen Cooley, sales manager, Nikon Instruments. "The P3 integrates early warning functionality into a single process tool and solves many of the problems associated with traditional lithography inspection."

The P3 is designed to determine optimum focus and exposure control, and to measure and analyze line width roughness for the 55nm node and beyond. The product has achieved a worldwide first with the successful development of an innovative pattern edge roughness (PER) optical system which provides pattern profile control considered indispensable for the 55 nm fab process. The P3 is very accurate with sensitivity in the 5 to 10nm range and allows users to bypass many of their SEM, Brightfield and manual inspection steps.

Accurate lithography inspection and analysis have become critical to process control as shrinking design rules and new technologies make cost-effective IC manufacturing more difficult to achieve. Nikon's P3 includes an automated macro defect inspection capability to detect particles, scratches and coating errors and rapidly identifies many common lithography manufacturing defects.

With high throughput of over 150wph and a full 100% wafer surface inspection capability with integrated backside inspection, the P3 accelerates the inspection process and improves product yields without comprising accuracy.

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About Nikon Instruments Inc.

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